EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	13	peterson near2 ingrid.in. hoff near2 (mike michael).in. wiley near2 jim.in.	US-PGPUB; USPAT	OR	OFF	2007/01/31 14:39
S2	4	"6268093".pn. "6373975".pn. "6701004".pn. "5965306".pn.	US-PGPUB; USPAT	OR	OFF	2006/12/27 18:45
S3	1	"20040091142"	US-PGPUB	OR	OFF	2007/01/31 17:04
S5	2480728	focus exposure illumination aperture coherence	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/17 10:09
S6	5708802	anomaly defect imperfection blemish crack deformity error fault flaw hole irregular$7 scratch contamina$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/17 10:12
S7	997466	photomask lithograph$3 semiconductor near mask pcb circuit near2 board reticle wafer	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/06/06 13:19
S8	11954984	different distinct many several plural$4 var$3 chang$3 distinctive various numerous separate	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/01/17 10:17
S9	273699	S8 near3 S5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/01/17 10:19
S10	148789	S6 with S7	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/01/17 10:18
S11	7	(subtract$3 tak$3 adj away remov$3) near3 (non-transient)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/17 17:40

S12	1	S9 and S10 and S11	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/17 10:20
S13	10220	S9 and S10	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/17 10:22
S14	451	(subtract$3 tak$3 adj away remov$3) near3 (hard near3 S6)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/17 17:43
S15	5	S13 and S14	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/17 10:25
S16	5708802	anomaly defect imperfection blemish crack deformity error fault flaw hole irregular$7 scratch contamina$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/25 13:39
S17	17875	(non-transient hard enduring non-fleeting non-evanescent) near3 S16	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/18 14:30
S18	453	(subtract$3 tak$3 adj away remov$3) near3 S17	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/20 11:59
S19	997466	photomask lithograph$3 semiconductor near mask pcb circuit near2 board reticle wafer	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/01/17 17:44
S20	38	S19 near3 S16 and S18	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/17 17:44

S21	37975	(transient non-transient soft hard brief enduring fleeting non-fleeting evanescent non-evanescent) near3 S16	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/24 16:25
S22	4	("5308722" | "6421457").PN. OR ("6701004").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/01/18 14:24
S23	5711627	anomaly defect imperfection blemish crack deformity error fault flaw hole irregular$7 scratch contamina$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/18 14:30
S24	22954	(transient soft brief fleeting evanescent) near3 S23	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/18 15:06
S25	17897	(non-transient hard enduring non-fleeting non-evanescent) near3 S23	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/06 15:24
S26	21	(subtract$3 tak$3 adj away remov$3) near3 S25 same S24	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/18 14:46
S27	1580	S24 same S25	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/18 15:06
S28	6952	382/141-145,147,149,182,185. ccls. 348/87,131.ccls. 359/436,385.ccls. 356/401.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/01/18 15:08
S29	5711627	anomaly defect imperfection blemish crack deformity error fault flaw hole irregular$7 scratch contamina$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/18 15:08
S30	22954	(transient soft brief fleeting evanescent) near3 S29	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/18 15:08

S31	17897	(non-transient hard enduring non-fleeting non-evanescent) near3 S29	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/18 15:08
S32	1580	S30 same S31	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/18 15:08
S33	6	S32 and S28	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/01/18 15:10
S34	1	(transient non-transient soft hard brief enduring fleeting non-fleeting evanescent non-evanescent) and "6701004".pn.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/29 11:13
S35	5725702	anomaly defect imperfection blemish crack deformity error fault flaw hole irregular$7 scratch contamina$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/31 12:15
S36	212	(transient non-transient soft hard brief enduring fleeting non-fleeting evanescent non-evanescent) near3 S35 and "382".clas.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/06/06 13:18
S37	1	("2004/0091142").URPN.	USPAT	OR	OFF	2007/01/31 13:33
S38	4	("5308722" | "6421457").PN. OR ("6701004").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/01/31 13:35
S39	6974	382/141-145,147,149,182,185. ccls. 348/87,131.ccls. 359/436,385.ccls. 356/401.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/01/31 14:40
S40	712	reference near3 compar$3 and S39	US-PGPUB; USPAT	OR	ON	2007/09/20 15:53
S41	5725702	anomaly defect imperfection blemish crack deformity error fault flaw hole irregular$7 scratch contamina$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/31 15:19

S43	1001769	photomask lithograph$3 semiconductor near mask pcb circuit near2 board reticle wafer	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR		OFF	2007/01/31 15:23
S44	144	reference near3 compar$3 with S41 and S39 and S43 near3 S41	US-PGPUB; USPAT	OR		ON	2007/01/31 15:52
S47	1981	(bin binning) with region	US-PGPUB; USPAT	OR		ON	2007/01/31 15:54
S48	12	S39 and S47	US-PGPUB; USPAT	OR		ON	2007/01/31 15:56
S49	182	(high bright) with (low dark) with (filter$3 remov$3) with (pre-process$3 preprocess$3)	US-PGPUB; USPAT	OR		ON	2007/01/31 15:58
S50	1	S39 and S49	US-PGPUB; USPAT	OR		ON	2007/01/31 15:58
S51	29	"382".clas. and S49	US-PGPUB; USPAT	OR		ON	2007/01/31 16:03
S52	12091	(multiple many several array) near3 (CCD sensor detector) with pixel	US-PGPUB; USPAT	OR		ON	2007/01/31 16:04
S53	157	S39 and S52	US-PGPUB; USPAT	OR		ON	2007/01/31 16:13
S54	1225	flag$3 with review$3	US-PGPUB; USPAT	OR		ON	2007/01/31 16:38
S55	15	S39 and S54	US-PGPUB; USPAT	OR		ON	2007/01/31 16:44
S56	267	(remov$3 filter$3) with (high same low) near3 intensity	US-PGPUB; USPAT	OR		ON	2007/01/31 16:48
S57	28	"382".clas. and S56	US-PGPUB; USPAT	OR		ON	2007/01/31 16:45
S58	49	(threshold$3) with (high same low) near3 intensity and "382". clas.	US-PGPUB; USPAT	OR		ON	2007/01/31 16:49
S59	9	(threshold$3) with (high same low) near3 intensity and S39	US-PGPUB; USPAT	OR		ON	2007/01/31 16:50
S61	40	S58 not S59	US-PGPUB; USPAT	OR		ON	2007/01/31 16:51
S66	60928	"382".clas. S39	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR		OFF	2007/01/31 17:12
S67	246	(remov$3 filter$3 threshold$3) near3 (dark same bright)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR		ON	2007/01/31 17:13

S68	12	(remov$3 filter$3 threshold$3) near3 (high same low) near3 (brightness lightness) and S66	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/31 17:13
S69	55	S67 and S66	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/31 17:18
S70	9	S69 and S39	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/01/31 17:18
S71	122	lithograph$3 near7 aerial adj image	US-PGPUB; USPAT	OR	ON	2007/05/22 16:34
S72	2	aerial adj image same non-aerial adj image	US-PGPUB; USPAT	OR	ON	2007/05/22 16:35
S73	1	"20040091142"	US-PGPUB; USPAT	OR	ON	2007/05/22 16:37
S74	6009	(photomask photoreticle reticle mask) near3 (defect$1 inspect $3)	US-PGPUB; USPAT	OR	ON	2007/05/22 16:39
S76	5862607	anomaly defect imperfection blemish crack deformity error fault flaw hole irregular$7 scratch contamina$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/05 16:15
S77	203	reticle near3 S76 and lithograph $3 and aerial adj imag$3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/05 16:16
S78	7191	382/141-145,147,149,182,185. ccls. 348/87,131.ccls. 359/436,385.ccls. 356/401.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/06/06 15:24
S79	27	S78 and S77	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/06 11:01

S80	1197	aerial adj image adj measur$6 adj system AIMS with (reticle mask)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/06 12:20
S81	5862607	anomaly defect imperfection blemish crack deformity error fault flaw hole irregular$7 scratch contamina$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/06 11:12
S82	37029	S81 near3 (mask reticle)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/06 11:42
S83	54	S80 same S82	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/06 11:45
S84	1	08/950620.app.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/06 11:45
S85	1037	aerial adj imag$3 with (reticle mask)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/06 11:50
S86	140	S85 same S82 not S83	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/06 11:50
S87	1	"5795688".pn.	USPAT	OR	OFF	2007/06/06 12:05
S88	1201	aerial adj imag$3 adj measur$6 adj system AIMS with (reticle mask)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/06 12:20
S89	5862607	anomaly defect imperfection blemish crack deformity error fault flaw hole irregular$7 scratch contamina$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/06 13:18

S90	39263	(transient non-transient soft hard brief enduring fleeting non-fleeting evanescent non-evanescent) near3 S89	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/20 15:51
S91	611729	photomask semiconductor near mask reticle mask	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/25 13:38
S93	18494	(non-transient hard enduring non-fleeting non-evanescent) near3 S89	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/06/06 13:26
S94	526	S93 near7 S91	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/06/06 13:27
S95	237	S93 near7 S91 with (non-aerial print$3 project$3 etch$3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/06/06 13:30
S96	0	S93 near7 S91 with (non-aerial)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/06/06 13:28
S97	7191	382/141-145,147,149,182,185. ccls. 348/87,131.ccls. 359/436,385.ccls. 356/401.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/06/06 13:28
S98	1	S95 and S97	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/06/06 13:29
S99	30	S93 and S97	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/06/06 13:30

S100	7191	382/141-145,147,149,182,185.ccls. 348/87,131.ccls. 359/436,385.ccls. 356/401.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/06/06 15:24
S101	5862607	anomaly defect imperfection blemish crack deformity error fault flaw hole irregular$7 scratch contamina$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/06 15:24
S102	18495	(non-transient hard enduring non-fleeting non-evanescent) near3 S101	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/06 15:28
S103	30	S102 and S100	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/06 15:25
S104	92	S100 and (pinhole pindot extrusion) same (mask reticle photomask)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/06/06 15:28
S106	1056	mask adj layout	USPAT	OR	OFF	2007/09/20 11:58
S108	5981851	anomaly defect imperfection blemish crack deformity error fault flaw hole irregular$7 scratch contamina$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/20 11:59
S109	19021	(non-transient hard enduring non-fleeting non-evanescent) near3 S108	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/20 11:59
S110	496	(subtract$3 tak$3 adj away remov$3) near3 S109	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/20 11:59
S111	7372	382/141-145,147,149,182,185.ccls. 348/87,131.ccls. 359/436,385.ccls. 356/401.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/20 15:18

S112	3	S110 and S111	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/20 12:00
S113	3616	aerial adj imag$3	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/20 15:18
S114	132689	(transient with non-transient soft with hard brief with enduring fleeting with non-fleeting evanescent with non-evanescent)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/20 15:59
S115	5304	(determin$3 locat$4 find$4 flag$4 extract$3) with S114	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/20 16:00
S116	7372	382/141-145,147,149,182,185. ccls. 348/87,131.ccls. 359/436,385.ccls. 356/401.ccls.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/09/20 15:53
S117	4	S116 and S115	US-PGPUB; USPAT	OR	ON	2007/09/20 15:53
S118	136	(determin$3 locat$4 find$4 flag$4 extract$3) with S114 same (reticle wafer mask photomask semiconductor)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/20 15:58
S119	5981851	anomaly defect imperfection blemish crack deformity error fault flaw hole irregular$7 scratch contamina$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/20 16:00
S120	1365	(transient near3 S119 with non-transient near3 S119 soft near3 S119 with hard near3 S119 brief near3 S119 with enduring near3 S119 fleeting near3 S119 with non-fleeting near3 S119 evanescent near3 S119 with non-evanescent near3 S119)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/20 16:00

S121	14	(determin$3 locat$4 find$4 flag$4 extract$3) with S120 same (reticle wafer mask photomask semiconductor)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/20 16:04
S122	158	(anomaly defect imperfection blemish crack deformity error fault flaw hole irregular$7 scratch contamina$5) near5 (bin$3 stor$4 flag$4) near3 (region area pixels pels) near3 (around surround$4 proximat$3 border $3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/25 13:41
S123	48	"382".clas. and S122	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/09/25 13:42
S124	3	"6902855".pn. "6757645".pn. "6171737".pn.	USPAT	OR	OFF	2008/01/19 19:39
S125	3	"6902855".pn. "6757645".pn. "6171737".pn.	US-PGPUB; USPAT	OR	ON	2008/01/24 11:43
S126	76	("20020019729" | "20020035461" | "4812962" | "5051598" | "5182718" | "5241185" | "5242770" | "5256505" | "5282140" | "5316878" | "5326659" | "5340700" | "5424154" | "5432714" | "5447810" | "5532090" | "5533148" | "5538815" | "5553273" | "5572598" | "5631110" | "5657235" | "5663893" | "5702848" | "5705301" | "5707765" | "5740068" | "5795688" | "5801954" | "5804340" | "5815685" | "5825647" | "5827623" | "5847959" | "5849440" | "5862058" | "5863682" | "6009250" | "6009251" | "6011911" | "6014456" | "6016357" | "6076465" | "6078738" | "6081658" | "6081659" | "6130750").PN. OR ("6757645").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/01/24 16:25
S127	6118438	anomaly defect imperfection blemish crack deformity error fault flaw hole irregular$7 scratch contamina$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/24 16:26

S128	7	(transient non-transient soft hard brief enduring fleeting non-fleeting evanescent non-evanescent) near3 S127 and S126	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/29 14:38
S130	76	("20020019729" | "20020035461" | "4812962" | "5051598" | "5182718" | "5241185" | "5242770" | "5256505" | "5282140" | "5316878" | "5326659" | "5340700" | "5424154" | "5432714" | "5447810" | "5532090" | "5533148" | "5538815" | "5553273" | "5572598" | "5631110" | "5657235" | "5663893" | "5702848" | "5705301" | "5707765" | "5740068" | "5795688" | "5801954" | "5804340" | "5815685" | "5825647" | "5827623" | "5847959" | "5849440" | "5862058" | "5863682" | "6009250" | "6009251" | "6011911" | "6014456" | "6016357" | "6076465" | "6078738" | "6081658" | "6081659" | "6130750").PN. OR ("6757645").URPN.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/01/29 11:11
S131	6124974	anomaly defect imperfection blemish crack deformity error fault flaw hole irregular$7 scratch contamina$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/29 11:12
S132	5244159	(transient non-transient soft hard brief enduring fleeting non-fleeting evanescent non-evanescent)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/29 11:13
S133	231198	(class$7 sort$3 identif$7 recogni $7 determin$7 find$3 search$3) near3 S131	US-PGPUB; USPAT; USOCR	OR	OFF	2008/01/29 11:15
S136	1	"6757645".pn. and print$8 with potential	US-PGPUB; USPAT	OR	ON	2008/01/29 11:21
S137	10	S130 and S132 with S131 and S133	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2008/01/29 15:58

S139	6124974	anomaly defect imperfection blemish crack deformity error fault flaw hole irregular$7 scratch contamina$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/29 14:42
S140	2	(transient non-transient soft hard brief enduring fleeting non-fleeting evanescent non-evanescent) near3 S139 with subtract$4 same (reticle mask photomask lithograph$3)	US-PGPUB; USPAT; USOCR	OR	ON	2008/01/29 14:43
S141	6124974	anomaly defect imperfection blemish crack deformity error fault flaw hole irregular$7 scratch contamina$5	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/29 16:00
S143	4735498	(transient non-transient soft hard brief enduring fleeting non-fleeting evanescent non-evanescent)	US-PGPUB; USPAT; USOCR	OR	ON	2008/01/29 16:01
S144	6	categor$5 near3 S143 same (photomask mask reticle)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/01/29 16:02

4/24/2008 8:53:23 PM
C:\Documents and Settings\kyuan\My Documents\EAST\Workspaces\10619943.wsp